

Amendments to the Specification:

Please replace the paragraph beginning at page 3, line 20, with the following rewritten paragraph:

-- Please refer to FIG. 3. A cleaning apparatus of the present invention 5 includes a sealed up body 50, a cleaning mechanism or cleaning mechanisms 52, and a vacuuming pump 54. In this embodiment, the cleaning mechanisms 52 are nozzles. --

Please replace the paragraph beginning at page 4, line 10, with the following 10 rewritten paragraph:

-- Please refer to FIG. 4, the cleaning system includes a combination of a substrate 64 and a frame layer 66, the sealed up body 50 and the cleaning mechanisms 52. The frame layer 66 is arranged on the substrate 64 to form a chamber 68 together with the substrate 64. The substrate 64 is located within the 15 cleaning room 62, and is mounted on an upper portion 50A of the sealed up body 50 with the chamber 68 facing downwards. In detail, the substrate 64 has a bottom surface 64B fixed to the upper portion 50A of the sealed up body 50, a top surface 64T fixed to the frame layer 66, and a side edge 64S aligned with a side edge 66S of the frame layer 66. Therefore, the cleaner from the cleaning 20 mechanism 52 is jetted out in a form of a stream moving in one and only one direction toward the chamber 68 of the combination of the substrate 64 and the frame layer 66 ejected to the chamber 68 so that the chamber 68 may be cleaned by the cleaner, which is ejected slantingly upwards. The one and only one direction is not perpendicular to the top surface 64T of the substrate 64. In this 25 embodiment, the vacuuming pump 54 is disposed in the cleaning room 62 and under the chamber 68 of the combination of the substrate 64 and the frame layer 66 and has a sucking port 55 for sucking the cleaner and the particles. The sucking port 55 is disposed between the two cleaning mechanisms 52, which are disposed in the cleaning room 62 and disposed below the combination of the substrate 64

and the frame layer 66 opposite to each other. --